Introduction to Integrating Knowledge and Learning Processes Minitrack

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After last year’s very successful first minitrack on this topic, we keep up the discussion concerning the integration of concepts, processes, and systems for the fields of knowledge management and e-learning. Consequently, this minitrack mainly focuses on two issues: a) how can knowledge and learning as well as business processes be integrated, and b) how can related ICT systems be integrated to enable an efficient workflow.

Using mobile and ubiquitous technologies can lead to a paradigm shift in the construction of such systems: from static to highly contextualized knowledge and learning experiences. Based on the integration of knowledge and learning systems into social networks and social media applications, formal and informal collaborative interactions will further enhance this effect.

The minitrack focuses on the adoption and diffusion of corresponding approaches. Leading question is: How knowledge, learning and business processes as well as the related ICT systems can be designed and interrelated for successful adoption and diffusion?

The two accepted papers – organized in one session – provide answers on this question taking current recent research and application projects into account:

The paper by HARNISCH, PUCHLEITNER, REINISCH AND UITZ (Model of a Personalization-based Agent System for Early Product Adoption Phases) presents how an agent could improve personalization in the trial phase of software as a service (SaaS) products, which again positively impacts user experience, efficiency and eventually supports the adoption decision.

Within his contribution Data Mining and Support Vector Regression Machine Learning in Semiconductor Manufacturing to improve Virtual Metrology, LENZ presents a mathematical approach to predict the thickness of dielectric layers on wafers in semiconductor manufacturing. Applying a a state-of-the-art Machine Learning regression algorithm provides promising results overcoming shortcomings of typical classification approaches.

We hope the selected contributions provide comprehensive insights into integrated knowledge and learning solutions that draw an audience and generate interesting discussions during HICSS-46.